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**Substitute for form 1449A/PTO**

## **INFORMATION DISCLOSURE STATEMENT BY APPLICANT**

*(use as many sheets as needed)*

Sheet 1 of 2

Complete if Known	
Application Number	09/698,317
Filing Date	October 27, 2000
First Named Inventor	Choi et al.
Group Art Unit	2859
Examiner Name	Unassigned <i>T. Doughty</i>
Attorney Docket Number	PA09-06V02

**U.S. PATENT DOCUMENTS**

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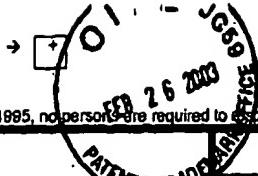
## FOREIGN PATENT DOCUMENTS

Examiner Signature	Thomas M. O'neil, Jr.	Date Considered	2-12-04
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<sup>1</sup>Unique citation designation number. <sup>2</sup>See attached Kinds of U.S. Patent Documents. <sup>3</sup>Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup>For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup>Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 18 if applicable.

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Substitute for form 1449B/PTO				Complete if Known	
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (use as many sheets as necessary)				Application Number	09/698,317
				Filing Date	October 27, 2000
				First Named Inventor	Choi et al.
				Group Art Unit	2859
				Examiner Name	Unassigned <i>T. Douglass</i>
Sheet	2	of	2	Attorney Docket Number	PA09-06V02

#### **OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS**

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
TMB	B10	LIN, "Multi-Layer Resist Systems", Introduction of Microlithography", American Chemical Society, 1983, pp. 287-350, IBM T.J. Watson Research Center, Yorktown Heights, New York 10598.
TMB	B11	COWIE, "Polymers: Chemistry and Physics of Modern Materials", 1991, pp. 408-409, 2 <sup>nd</sup> Ed, Chapman and Hall, a division of Routledge, Chapman and Hall, Inc., 29 West 35 <sup>th</sup> Street, NY, NY 10001-2291.
TMB	B12	CHOU et al., "Imprint of Sub-25 nm Vias and Trenches in Polymers", Applied Physics Letters, November 20, 1995, pp. 3114-3116, vol. 67(21).
TMB	B13	CHOU et al., "Imprint Lithography with 25-Nanometer Resolution", Science, Apr. 5, 1996, pp. 85-87, vol. 272.
TMB	B14	CHOU et al., "Imprint Lithography with Sub-10nm Feature Size and High Throughput", Microelectronic Engineering, 1997, pp. 237-240, vol. 35.
TMB	B15	XIA et al., "Soft Lithography", Agnew. Chem. Int. Ed., 1998, pp. 550-575, vol. 37.
		TECHNOLOGY CENTER RECEIVED FEB 3 2003 MAR 07 2003 RECEIVED TC 1700

Examiner Signature	Thomas M. Dougherty	Date Considered	2-12-04
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<sup>1</sup>Unique citation designation number. <sup>2</sup>Applicant is to place a check mark here if English language Translation is attached.

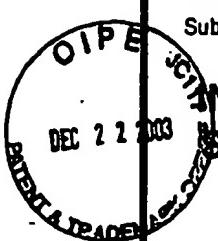
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**Substitute for form 1449A/PTO**

## **INFORMATION DISCLOSURE STATEMENT BY APPLICANT**

(use as many sheets as necessary)

Sheet

1

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2

<i><b>Complete if Known</b></i>	
<b>Application Number</b>	09/698,317
<b>Filing Date</b>	October 27, 2000
<b>First Named Inventor</b>	Choi et al.
<b>Group Art Unit</b>	2834
<b>Examiner Name</b>	Dougherty, Thomas M.
<b>Attorney Docket Number</b>	UTS-09-06V02

## **U.S. PATENT DOCUMENTS**

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>1</sup>Unique citation designation number. <sup>2</sup>See attached Kinds of U.S. Patent Documents. <sup>3</sup>Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup>For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup>Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. <sup>6</sup>Applicant is to place a check mark here if English language Translation is attached.

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Substitute for form 1449B/PTO		<i>Complete if Known</i>	
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b> <i>DEC 12 2003</i> <i>(use as many sheets as necessary)</i>		Application Number	09/698,317
		Filing Date	October 27, 2000
		First Name Inventor	Choi et al.
		Group Art Unit	2834
		Examiner Name	Dougherty, Thomas M.
Sheet	2	of	2
		Attorney Docket Number	
		UTS-09-06V02	

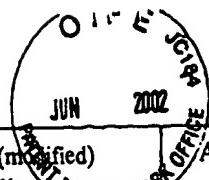
**OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS**

Examiner Signature	Ghommam Rezvani	Date Considered	Sept. 12, 2004
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**\*EXAMINER:** Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>1</sup>Unique citation designation number. <sup>2</sup>Applicant is to place a check mark here if English language Translation is attached.

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Form PTO-1449 (modified) List of Patents and Publications For Applicant's Information Disclosure Statement (Use several sheets if necessary)			ATTY. DKT. NO. 5119-08601	SERIAL NO. 09/698,317			
			APPLICANT: Choi et al.	GROUP: 2859			
			FILING DATE: October 27, 2000				
U.S. PATENT DOCUMENTS							
EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>JMP</i>	A1	3,807,027	4/1974	Heisler	29	423	
<i>JMP</i>	A2	3,807,029	4/1974	Troeger	29	436	
<i>JMP</i>	A3	3,811,665	5/1974	Seelig	26	RECEIVED	
<i>JMP</i>	A4	4,062,600	12/1977	Wyse	384	206	JUN 26 2002
<i>JMP</i>	A5	4,098,001	7/1978	Watson	33	644	
<i>JMP</i>	A6	4,155,169	5/1979	Drake et al.	33	GROUP 3600	
<i>JMP</i>	A7	4,202,107	5/1980	Watson	33	644	
<i>JMP</i>	A8	4,267,212	5/1981	Sakawaki	427	240	
<i>JMP</i>	A9	4,337,579	7/1982	De Fazio	33	644	
<i>JMP</i>	A10	4,355,469	10/1982	Nevins et al.	267	150	
<i>JMP</i>	A11	4,414,750	11/1983	De Fazio	267	166	
<i>JMP</i>	A12	4,451,507	5/1984	Beltz et al.	427	240	
<i>JMP</i>	A13	4,610,442	9/1986	Oku et al.	269	73	
<i>JMP</i>	A14	4,694,703	11/1987	Routson	74	5F	
<i>JMP</i>	A15	4,731,155	3/1988	Napoli et al.	266	44	
<i>JMP</i>	A16	4,763,886	8/1988	Takei	269	73	
<i>JMP</i>	A17	4,929,083	5/1990	Brunner	356	400	
<i>JMP</i>	A18	4,959,252	11/1990	Bonnebat et al.	428	64.7	
<i>JMP</i>	A19	5,072,126	12/1991	Progler	250	548	
<i>JMP</i>	A20	5,110,514	5/1992	Soane	264	496	
<i>JMP</i>	A21	5,126,006	6/1992	Cronin et al.	438	702	
<i>JMP</i>	A22	5,204,739	4/1993	Domenicali	348	79	
<i>JMP</i>	A23	5,240,550	8/1993	Boehnke et al.	216	24	
<i>JMP</i>	A24	5,348,616	9/1994	Hartman et al.	216	48	
<i>JMP</i>	A25	5,392,123	2/1995	Marcus et al.	356	625	
<i>JMP</i>	A26	5,425,964	6/1995	Southwell et al.	427	10	
<i>JMP</i>	A27	5,452,090	9/1995	Progler et al.	356	401	

EXAMINER:

Thomas M. Ruggarty

DATE CONSIDERED:

Feb. 13, 2001

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Form PTO-1449 (modified)			ATTY. DKT. NO. 5119-08601	SERIAL NO. 09/698,317		
List of Patents and Publications For Applicant's Information Disclosure Statement JUN 21 2002 (Use several sheets if necessary)			APPLICANT: Choi et al.	GROUP: 2859		
INFORMATION SHEET FOR INFORMATION DISCLOSURE STATEMENT						
III. PATENT DOCUMENTS						
EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS
TMB	A28	5,480,047	1/1996	Tanigawa et al.	216	12
TMB	A29	5,512,131	4/1996	Kumar et al.	438	RECEIVED
TMB	A30	5,515,167	5/1996	Ledger et al.	356	595
TMB	A31	5,545,367	10/1996	Bae et al.	261	481
TMB	A32	5,566,584	10/1996	Briganti et al.	74	990.1
TMB	A33	5,633,505	5/1997	Chung et al.	250	491.1
TMB	A34	5,724,145	3/1998	Kondo et al.	356	632
TMB	A35	5,753,014	5/1998	Van Rijn	96	12
TMB	A36	5,760,500	6/1998	Kondo et al.	310	12
TMB	A37	5,772,905	6/1998	Chou	216	44
TMB	A38	5,776,748	7/1998	Singhvi et al.	435	180
TMB	A39	5,779,799	7/1998	Davis	118	663
TMB	A40	5,802,914	9/1998	Fassler et al.	74	110
TMB	A41	5,877,036	3/1999	Kawai	438	16
TMB	A42	5,877,861	3/1999	Ausschnitt et al.	356	401
TMB	A43	5,888,650	3/1999	Calhoun et al.	428	354
TMB	A44	5,900,160	5/1999	Whitesides et al.	216	41
TMB	A45	5,912,049	6/1999	Shirley	427	240
TMB	A46	5,942,871	8/1999	Lee	318	611
TMB	A47	5,948,470	9/1999	Harrison et al.	427	148
TMB	A48	5,952,127	9/1999	Yamanaka	430	5
TMB	A49	6,038,280	3/2000	Rossiger et al.	378	50
TMB	A50	6,039,897	3/2000	Lochhead et al.	264	1,24
TMB	A51	6,046,056	4/2000	Parce et al.	204	402.05
TMB	A52	6,051,345	4/2000	Huang	430	5
TMB	A53	6,074,827	6/2000	Nelson et al.	435	6
TMB	A54	6,091,485	7/2000	Li et al.	356	73
	A55	6,128,085	10/2000	Buermann et al.	356	369

EXAMINER:

*Thomas M. Bergelt*

DATE CONSIDERED:

Feb. 13, 2004

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Form PTO-1449 (modified)		ATTY. DKT. NO. 5119-08601	SERIAL NO. 09/698,317
List of Patents and Publications For Applicant's Information Disclosure Statement JUN 21 2002 (Use several sheets if necessary)		APPLICANT: Choi et al.	GROUP: 2859
FILING DATE: October 27, 2000			

U.S. PATENT DOCUMENTS							
EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
JMD	A56	6,143,412	11/2000	Schueller et al.	428	408	RECEIVED
JMD	A57	6,168,845	1/2001	Fontana, Jr. et al.	428	65,5	
JMD	A58	6,180,239	1/2001	Whitesides et al.	428	411,1	JUN 26 2002
JMD	A59	6,204,922	3/2001	Chalmers	356	730	GROUP 3600
JMD	A60	6,334,960	1/2002	Wilson et al.	216	52	

## FOREIGN PATENT DOCUMENTS

EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES/NO
JMD	A61	00/54107	9/2000	WO	600F	7/02	
JMD	A62	01/33232	5/2001	WO	601R	—	
JMD	A63	01/33300	5/2001	WO	402K	5/24	
JMD	A64	244884	3/1987	EP	82AC	33/34	
JMD	A65	733455	9/1996	EP	82AC	33/34	NO
JMD	A66	2800476	7/1978	DE	603C	5/08	NO
JMD	A67	19648844	11/1999	DE	82AC	59/02	NO
JMD	A68	1-196749	8/1989	JP	611B	7/26	NO

EXAMINER: *Thomas M. Dayhut*

DATE CONSIDERED:

*Feb. 13, 2004*

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<b>Form PTO-1449 (modified)</b> List of Patents and Publications For Applicant's Information Disclosure Statement JUN 21 2002 (Use several sheets if necessary)			ATTY. DKT. NO. 5119-08601 <b>APPLICANT:</b> Choi et al. <b>FILING DATE:</b> October 27, 2000	SER. NO. 09/698,317 <b>RECEIVED</b> GROUP 2859 26 2002 <b>GROUP 3600</b>
<b>OTHER ART</b> (Including Author, Title, Date, Pertinent Pages, Etc.)				
	A69	Stewart, D.; "A Platform with Six Degrees of Freedom", Proc. of Inst. Mech. Engrs., 1965, 180, 371-378.		
	A70	Paros, J.M.; Weisbord, L.; "How to Design Flexure Hinges", Machine Design, 1965, 151-156.		
	A71	Raibert, M.H.; Craig, J.J.; "Hybrid Position/Force Control of Manipulators", 1981, 102, 126-133.		
	A72	Hogan, Neville; "Impedance Control: An Approach to Manipulation", Journal of Dynamic Systems, Measurement and Control, 1985, 107, 1-7.		
	A73	Hollis, Ralph; Salcudean, S.E.; Allan, A.P.; "A Six-Degree-of-Freedom Magnetically Levitated Variable Compliance Fine-Motion Wrist: Design, Modeling and Control", IEEE Transactions on Robotics and Automation, 1991, 7, 320-332.		
	A74	Tomita, Y. et al.; "6-Axes Motion Control Method for Parallel-Linkage-Type Fine Motion Stage", Journal of Japan Society of Precision Engineering, 1992, 118-124.		
	A75	Slocum, Alexander; "Precision Machine Design: Macromachine Design Philosophy and its Applicability to the Design of Micromachines", Proc. of IEEE Micro Electro Mech. Systems Workshop, 1992, 37-42.		
	A76	Krug, Herbert; Merl, Norbert; Schmidt, Helmut; "Fine Patterning of Thin Sol-Gel Films", Journal of Non-Crystalline Solids, 1992, 447-450.		
	A77	Arai, T.; Laronneur, R.; Jaya, Y.M.; "Calibration and Basic Motion of a Micro Hand Module", Proc. of IECON, 1993, 1660-1665.		
	A78	Peng, Zhi-Xin; Adachi, N.; "Compliant Motion Control of Kinematically Redundant Manipulators", IEEE Transactions on Robotics and Automation, 1993, 9, 831-837.		
	A79	Rong, Y.; Zhu, Y.; Luo, Z.; Liu, X.; "Design and Analysis of Flexure-Hinge Mechanism Used in Micro-Positioning Stages", ASME, 1994, 2, 979-985.		
	A80	Hashimoto, M.; Imamura, Y.; "Design and Characteristics of a Parallel Link Compliant Wrist", IEEE International Conference on Robotics and Automation, 1994, 2457-2462.		
	A81	Merlet, J.P.; "Parallel Manipulators: State of the Art and Perspectives", Advanced Robotics, 1994, 8, 589-596.		
	A82	Ananthasuresh, S.; Kikuchi, N.; "Strategies for Systematic Synthesis of Compliant MEMS", ASME, 1994, 2, 677-686.		
	A83	Arai, T.; Tanikawa, T.; Merlet, J.P.; Sendai, T., "Development of a New Parallel Manipulator with Fixed Linear Actuator", Proc. of Japan/USA Symposium on Flexible Automation, 1996, 1, 145-149.		
	A84	Howell, L.L.; Midha, A.; "Loop-Closure Theory of the Analysis and Synthesis of Compliant Mechanisms", Journal of Mechanical Design, 1996, 118, 121-125.		
	A85	Haisma, J. et al.; "Mold-Assisted Nanolithography: A Process for Reliable Pattern Replication", Journal of Vacuum Science and Technology, 1996, 14, 4124-4128.		
	A86	Pernette, Eric; Henein, Simon; Magnani, Ivo; Clavel, Reymond; "Design of Parallel Robots in Microrobotics", Robotica, 1997, 15, 417-420.		

EXAMINER:

DATE CONSIDERED: Feb. 13, 2004

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<b>Form PTO-1449 (modified)</b> List of Patents and Publications For Applicant's Information Disclosure Statement (Use several sheets if necessary)		
ATTY. DKT. NO. 5119-08601 SERIAL NO. 09/698,317 JUN 26 2002 APPLICANT: Choi et al. GROUP 2859 FILING DATE: October 27, 2000 <b>RECEIVED</b> <b>GROUP 3600</b>		
	A87	Rong, L.; Guang, H.; "Dynamics of Parallel Mechanism with Direct Compliance Control", IEEE, 1997, 1753-1758.
	A88	Mittal, Samir; Menq, Chia-Hsiang; "Precision Motion Control of Magnetic Suspension Actuator Using a Robust Nonlinear Compensation Scheme", IEEE/ASME Transactions on Mechatronics, 1997, 2, 268-280.
	A89	Physik Instruments, Product Catalog for Micropositioning, 1997.
	A90	Williams, Mark et al.; "Six Degree of Freedom Mag-Lev Stage Development", SPIE, 1997, 3051, 856-867.
	A91	Lee, Chang-Woo; Kim, Seung-Woo; "Ultraprecision Stage for Alignment of Wafers in Advanced Microlithography", Precision Engineering, 1997, 21, 113-122.
	A92	Kanetomo, M.; Kashima, H.; Suzuki, T.; "Robot for Use in Ultrahigh Vacuum", Solid State Tech., 1997, 63-72.
	A93	Goldfarb, M.; Speich, J.; "Compliant Micromanipulator Design for Scaled Bilateral Telemanipulation of Small-Scale Environments", ASME, Dynamic Systems and Control Div., 1998, 64, 213-218.
	A94	Koseki, Y. et al.; "Design and Accuracy Evaluation of High-Speed and High Precision Parallel Mechanism", Proc. of IEEE, Intl. Conf. on Robotics & Automation, 1998, 1340-1345.
	A95	Kim, Won-Jong; Trumper, David; "High Precision Magnetic Levitation Stage for Photolithography", Precision Engineering, 1998, 22, 66-77.
	A96	Mansky, P. et al.; "Large-Area Domain Alignment in Block Copolymer Thin Films Using Electric Fields", Macromolecules, 1998, 31, 4399-4401.
	A97	Wang, W.; Loh, R.; Gu, E.; "Passive Compliance Versus Active Compliance in Robot-Based Automated Assembly Systems", Industrial Robot, 1998, 25, 48-57.
	A98	Scheer, H.C. et al.; "Problems of Nanoimprinting Technique for Nanometer Scale Pattern Definition", Journal of Vacuum Science and Technology, 1998, 16, 3917-3921.
	A99	Xia, Y.; Whitesides, George; "Soft Lithography", Annu. Rev. Mater. Sci., 1998, 28, 153-184.
	A100	Tajbakhsh, H. et al.; "Three-Degree-of-Freedom Optic Mount for Extreme Ultraviolet Lithography", ASPE, 1998, 18, 359-362.
	A101	Lee, Dong Sung et al.; "Ultra Precision Positioning System for Servo Motor-Piezo Actuator Using Dual Servo Loop and Digital Filter Implementation", ASPE, 1998, 18, 287-290.
	A102	Wu, Wei et al.; "Large Area High Density Quantized Magnetic Disks Fabricated Using Nanoimprint Lithography", 1998, Journal of Vacuum Science and Technology, 1998, 16, 3825-3829.
	A103	Ohya, Y. et al.; "Development of 3-DOF Finger Module for Micro Manipulation", Proc. of IEEE, Intl. Conf. on Intelligent Robots and Systems, 1999, 894-899.
	A104	Tanikawa, T. et al.; "Development of Small-Sized 3 DOF Finger Module in Micro Hand for Micro Manipulation", Proc. of IEEE, Intl. Conf. on Intelligent Robots and Systems, 1999, 876-881.
	A105	Colburn, M. et al.; "Step and Flash Imprint Lithography: New Approach to High-Resolution Patterning", Proc. of SPIE, 1999, 3676, 379-389.

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Form PTO-1449 (modified)		ATTY. DKT. NO. 5119-0860	RECEIVED	SERIAL NO. 09/698,317
List of Patents and Publications For Applicant's Information Disclosure Statement (Use several sheets if necessary)		APPLICANT: Choi et al.	JUN 26 2002	GROUP: 2859
		FILING DATE: October 27, 2000	GROUP	3600
DNP	A106	Lucas Aerospace, Free-Flex Pivot Catalog, 1999		
TMB	A107	Goldfarb, M.; Speich, J.E.; "A Well-Behaved Revolute Flexure Joint for Compliant Mechanism Design", Journal of Mech. Design, 1999, 121, 424-429.		
TMB	A108	Geodetic Technology, G1000-PS Power Series Specifications, 1999, from <a href="http://www.hexapods.com">www.hexapods.com</a>		
TMB	A109	Hexel Corporation, Tornado 2000 System Specifications, 1999, from <a href="http://www.hexel.com">www.hexel.com</a>		
TMB	A110	Physik Instruments, PI Online-Catalog, 1999, from <a href="http://www.physikinstruments.com">www.physikinstruments.com</a>		
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*Thomas M. Bergman*

DATE CONSIDERED:

Feb. 13, 2004

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